

L Number	Hits	Search Text	DB	Time stamp
-	51785	((mask\$3 or resist\$3 or photoresist) same ((etch\$3 or chemical\$2 adj mil\$3 or deoxidiz\$3 or anodiz\$3) and metal)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/06/03 09:04
-	25136	((mask\$3 or resist\$3 or photoresist) same ((etch\$3 or chemical\$2 adj mil\$3 or deoxidiz\$3 or anodiz\$3) and metal)) and (mask\$3 or resist\$3 or photoresist) same (aluminum or "Al" or steel or titanium or "Ti"))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/06/03 09:05
-	26	((mask\$3 or resist\$3 or photoresist) same ((etch\$3 or chemical\$2 adj mil\$3 or deoxidiz\$3 or anodiz\$3) and metal)) and (mask\$3 or resist\$3 or photoresist) same (aluminum or "Al" or steel or titanium or "Ti")) and (mask\$3 or resist\$3 or photoresist) same (\$4urethane adj3 \$4acrylate or \$4urethane adj3 \$4acrylate)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/05/26 16:28
-	922	((mask\$3 or resist\$3 or photoresist) same ((etch\$3 or chemical\$2 adj mil\$3 or deoxidiz\$3 or anodiz\$3) and metal)) and (mask\$3 or resist\$3 or photoresist) same (aluminum or "Al" or steel or titanium or "Ti")) and (mask\$3 or resist\$3 or photoresist) same (\$4acrylate or \$4acrylate)) not (((mask\$3 or resist\$3 or photoresist) same ((etch\$3 or chemical\$2 adj mil\$3 or deoxidiz\$3 or anodiz\$3) and metal)) and (mask\$3 or resist\$3 or photoresist) same (aluminum or "Al" or steel or titanium or "Ti")) and (mask\$3 or resist\$3 or photoresist) same (\$4urethane adj3 \$4acrylate or \$4urethane adj3 \$4acrylate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/05/26 16:27
-	26	((mask\$3 or resist\$3 or photoresist) same ((etch\$3 or chemical\$2 adj mil\$3 or deoxidiz\$3 or anodiz\$3) and metal)) and (mask\$3 or resist\$3 or photoresist) same (aluminum or "Al" or steel or titanium or "Ti")) and (mask\$3 or resist\$3 or photoresist) same (\$4urethane adj3 \$4acrylate or \$4urethane adj3 \$4acrylate)) and (mask\$3 or resist\$3 or photoresist) same (peel\$4 or pull\$4 or remov\$4 or lift\$3 adj off)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/05/26 16:32
-	854	((mask\$3 or resist\$3 or photoresist) same ((etch\$3 or chemical\$2 adj mil\$3 or deoxidiz\$3 or anodiz\$3) and metal)) and (mask\$3 or resist\$3 or photoresist) same (aluminum or "Al" or steel or titanium or "Ti")) and (mask\$3 or resist\$3 or photoresist) same (\$4acrylate or \$4acrylate)) not (((mask\$3 or resist\$3 or photoresist) same ((etch\$3 or chemical\$2 adj mil\$3 or deoxidiz\$3 or anodiz\$3) and metal)) and (mask\$3 or resist\$3 or photoresist) same (aluminum or "Al" or steel or titanium or "Ti")) and (mask\$3 or resist\$3 or photoresist) same (\$4urethane adj3 \$4acrylate or \$4urethane adj3 \$4acrylate))) and (mask\$3 or resist\$3 or photoresist) same (peel\$4 or pull\$4 or remov\$4 or lift\$3 adj off)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/05/26 16:32

-	6	(((((mask\$3 or resist\$3 or photoresist) same ((etch\$3 or chemical\$2 adj mil\$3 or deoxidiz\$3 or anodiz\$3) and metal)) and (mask\$3 or resist\$3 or photoresist) same (aluminum or "Al" or steel or titanium or "Ti")) and (mask\$3 or resist\$3 or photoresist) same (\$4urethane adj3 \$4acrylate or \$4urethane adj3 \$4acrylate)) and (mask\$3 or resist\$3 or photoresist) same (peel\$4 or pull\$4 or remov\$4 or lift\$3 adj off)) and (mask\$3 or resist\$3 or photoresist) same (scrib\$4 or cut\$4 or mark\$4 or scrap\$4)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/05/26 16:34
-	1560	(mask\$3 or resist\$3 or photoresist) same ((deoxidiz\$3 or anodiz\$3) and metal)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/06/03 09:55
-	308	((mask\$3 or resist\$3 or photoresist) same ((deoxidiz\$3 or anodiz\$3) and metal)) and (peel\$4 or remov\$4 or scrib\$4) adj3 (mask\$3 or resist\$3 or photoresist)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/06/03 09:10
-	495	((mask\$3 or resist\$3 or photoresist) same ((deoxidiz\$3 or anodiz\$3) and metal)) and (peel\$4 or remov\$4 or scrib\$4 or pull\$4 or lift\$3 adj off) near3 (mask\$3 or resist\$3 or photoresist)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/06/03 09:11
-	511	((mask\$3 or resist\$3 or photoresist) same ((deoxidiz\$3 or anodiz\$3) and metal)) and (peel\$4 or remov\$4 or scrib\$4 or pull\$4 or lift\$3 adj off or cut\$4 or scrap\$4) near3 (mask\$3 or resist\$3 or photoresist)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/06/03 09:12
-	24	((mask\$3 or resist\$3 or photoresist) same ((deoxidiz\$3 or anodiz\$3) and metal)) and (peel\$4 or remov\$4 or scrib\$4 or pull\$4 or lift\$3 adj off or cut\$4 or scrap\$4) near3 (mask\$3 or resist\$3 or photoresist) same (seal\$3)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/06/03 09:19
-	1	(maskant or mask) and line adj sealant, same ((deoxidiz\$3 or anodiz\$3) and metal)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/06/03 09:57
-	0	(maskant or mask) and line adj sealer same ((deoxidiz\$3 or anodiz\$3) and metal)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/06/03 10:29
-	92	(216/42,44,47,48,101-102 or 430/320,323-324 or 205/122,135,153,188,320,324).ccls. and seal\$3 same mask\$3	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/06/03 19:08
-	145	(IRGACURE adj "1700") or (IRACURE adj "1700")	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/06/04 18:11
-	23	((IRGACURE adj "1700") or (IRACURE adj "1700")) and (wax or (synergist and triethanolamine))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/06/04 18:12